

MNC 2021 (October 26-29, Online and On-demand) Schedule

Tuesday, October 26

On-demand Session		
Keynote Session		
Poster Session		

Wednesday, October 27

Room A		
27A-1: Opening & Plenary Session 10:00-12:10		
Lunch Time		
Room A	Room B	Room C
27A-2: 13:30-15:15 Symp. A. EUVL Stochastics Symposium: Overcoming the Challenge of Stochastics for High Resolution EUV Lithography I	27B-2: 13:40-14:40 Nanofabrication I	27C-2: 13:30-14:50 CNT & TMDC I
27A-3: 15:45-17:15 Symp. A. EUVL Stochastics Symposium: Overcoming the Challenge of Stochastics for High Resolution EUV Lithography II	27B-3: 15:10-16:10 Nanofabrication II	27C-3: 15:30-18:00 Symp. B. Forefront of Low-Dimensional Nanomaterials for Future Applications
27A-4: 18:30-20:00 Symp. A. EUVL Stochastics Symposium: Overcoming the Challenge of Stochastics for High Resolution EUV Lithography III	27B-4: 16:10-17:10 Nanofabrication III	

Thursday, October 28

Room A	Room B	Room C
28A-1: 9:00-10:30 Symp. A. EUVL Stochastics Symposium: Overcoming the Challenge of Stochastics for High Resolution EUV Lithography IV	28B-1: 9:00-10:10 TMDC II	
28A-2: 11:00-12:30 Symp. A. EUVL Stochastics Symposium: Overcoming the Challenge of Stochastics for High Resolution EUV Lithography V	28B-2: 10:30-11:30 Graphene, Nanocarbon	28C-2: 11:00-12:00 BioMEMS, Lab on a Chip, and Nanobiotechnolog I
Lunch Time		
28A-3: 13:30-15:00 Symp. A. EUVL Stochastics Symposium: Overcoming the Challenge of Stochastics for High Resolution EUV Lithography VI	28B-3: 13:30-15:00 Nanowires/Quantum Dots	28C-3: 13:30-15:00 BioMEMS, Lab on a Chip, and Nanobiotechnolog II
28A-4: 15:15-16:45 Symp. A. EUVL Stochastics Symposium: Overcoming the Challenge of Stochastics for High Resolution EUV Lithography VII, Panel Discussion	28B-4: 15:30-17:00 Nanoelectronics	28C-4: 16:00-18:00 Symp. C. Biological Phenomena and Functions within Micro- and Nanospace
28A-5: 17:15-19:15 Symp. D. Enhancing technology for Next Generation Lithography I	28B-5: 18:30-22:10 Atomic Layer Processing (ALP) Part I and Part II	

Friday, October 29

Room A	Room B	Room C
29A-1: 9:00-10:30 Symp. D. Enhancing technology for Next Generation Lithography II		29C-1: 9:00-10:20 Microsystem Technology and MEMS Session I
29A-2: 11:00-12:30 Patterning Materials	29B-2: 10:10-12:20 NanoTool	29C-2: 11:00-12:00 Microsystem Technology and MEMS Session II
Lunch Time		
29A-3: 13:30-15:00 Advanced Photolithography	29B-3: 13:30-15:20 Nanomaterials	29C-3: 13:30-14:50 Microsystem Technology and MEMS Session III
29A-4: 15:30-17:00 Electron and Ion Beam Technologies	29B-4: 15:40-17:30 Nano Devices	29C-4: 15:30-17:20 Organic Nanomaterials
29A-5: 17:30-20:00 Nanoimprint, Hybrid-NIL, Biomimetics, and Functional Surfaces		